Refine Search

Search Results -

Terms	Documents
(hardmask same ((first or second or another) near3 photoresist) same trench).clm.	8

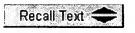
US Pre-Grant Publication Full-Text Database
US Patents Full-Text Database
US OCR Full-Text Database

Database:

EPO Abstracts Database
JPO Abstracts Database
Derwent World Patents Index
IBM Technical Disclosure Bulletins

Search:

L3				Refine Search
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Search History

DATE: Wednesday, August 16, 2006 Printable Copy Create Case

Name side by side	Query	Hit Count	Set Name result set
DB=P	GPB; PLUR=YES; OP=ADJ		
<u>L3</u>	(hardmask same ((first or second or another) near3 photoresist) same trench).clm.	8	<u>L3</u>
<u>L2</u>	(hardmask same ((first or second or anther) near3 photoresist) same trench).clm.	8	<u>L2</u>
<u>L1</u>	"10603041"	1	<u>L1</u>

END OF SEARCH HISTORY